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## (54) METHOD FOR MANUFACTURING CYCLIC OLEFIN POLYMER

## (57)Abstract:

PROBLEM TO BE SOLVED: To provide a method for manufacturing a cyclic olefin polymer showing heat resistance and lowering of the molecular weight and having little residual solvent. SOLUTION: A cyclic olefin polymer composition comprising a cyclic olefin polymer and an organic solvent is subjected to (1) heating with agitation at  $\geq 20^{\circ}$ C and not more than the boiling point of the composition under normal pressure, and then to heating under reduced pressures with continued agitation in a stepwise manner of (2) at  $\geq 80^{\circ}$ C and  $\leq 255^{\circ}$ C under a pressure of  $\geq 4$  kPa and  $\leq 190^{\circ}$ C and  $\leq 255^{\circ}$ C under a pressure of  $\geq 1$  kPa and  $\leq 190^{\circ}$ C and  $\leq 190^{\circ}$ C and  $\leq 190^{\circ}$ C under a pressure of  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C under a pressure of  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C under a pressure of  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C under a pressure of  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C under a pressure of  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C under a pressure of  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C under a pressure of  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C under a pressure of  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C and  $\leq 10^{\circ}$ C under a pressure of  $\leq 10^{\circ}$ C and  $\leq$ 

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